

WHAT IS CLAIMED IS:

1. A method of forming a resist pattern on a substrate, comprising the steps of:
forming a resist film on the substrate;
supplying a developing solution onto the resist film; and
submerging the substrate and the resist film formed thereon in a rinsing liquid kept in a rinsing tank; and
applying ultrasonic vibration to the rinsing liquid to rinse the developing solution from the resist film submerged in the rinsing liquid.
2. The method of Claim 1, wherein said step of applying ultrasonic vibration is conducted by applying ultrasonic vibration to said rinsing tank.
3. An apparatus for forming a resist pattern on a substrate comprising:
a rinsing tank which keeps rinsing liquid for rinsing developing solution remaining on a resist film formed on the substrate; and
an ultrasonic vibration mechanism which applies ultrasonic vibration to the rinsing liquid kept in said rinsing tank.
4. The apparatus of Claim 3, wherein said ultrasonic vibration mechanism applies ultrasonic vibration to said rinsing tank.